

Resource Summary Report

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Oxford: Ionfab 300 IBE Plasma Technology

RRID:SCR_020357

Type: Tool

Proper Citation

Oxford: Ionfab 300 IBE Plasma Technology (RRID:SCR_020357)

Resource Information

URL: <https://plasma.oxinst.com/products/ibe/ionfab-300>

Proper Citation: Oxford: Ionfab 300 IBE Plasma Technology (RRID:SCR_020357)

Description: Ion beam etch offers flexibility coupled with uniformity and is suitable for wide range of applications. Systems have flexible hardware options including open load, single substrate load lock and cassette to cassette. System specifications are closely tuned to applications, enabling faster and repeatable process results.

Resource Type: instrument resource

Keywords: Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

Availability: Commercially available

Resource Name: Oxford: Ionfab 300 IBE Plasma Technology

Resource ID: SCR_020357

Alternate IDs: Model_Number_Ionfab_300_IBE

Record Creation Time: 20220129T080349+0000

Record Last Update: 20260801T190648+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: Ionfab 300 IBE Plasma Technology.

No alerts have been found for Oxford: Ionfab 300 IBE Plasma Technology.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.